Special Issue

Plasma Science and Plasma-Assisted Applications

Message from the Guest Editors

Plasma science continues to evolve and expand, driven by ongoing research and technological advancements. As our understanding of plasmas deepens, new applications and innovations are being discovered, offering exciting possibilities for addressing challenges and advancing various scientific and technological frontiers. This Special Issue on "Plasma Science and Plasma-Assisted Applications" is aimed to focus on the recent developments and research on plasma physics, plasma chemistry, plasma technology and plasma applications in, but not limited to, energy, combustion, aerospace, biology, medicine, manufacturing, fluid mechanics and environmental science. **Keywords**

- plasma technology
- plasma physics
- plasma chemistry
- plasma applications
- plasma-assisted combustion
- plasma-treated water
- plasma coating
- plasma medicine
- plasma processing
- plasma diagnostics

Guest Editors

Dr. Ying-Hao Liao

Dr. Kun-Mo Lin

Prof. Dr. Jian-Zhang Chen

Dr. Katsuyuki Takahashi

Deadline for manuscript submissions

30 December 2025



Processes

an Open Access Journal by MDPI

Impact Factor 2.8 CiteScore 5.5



mdpi.com/si/174605

Processes
Editorial Office
MDPI, Grosspeteranlage 5
4052 Basel, Switzerland
Tel: +41 61 683 77 34

mdpi.com/journal/processes

processes@mdpi.com





Processes

an Open Access Journal by MDPI

Impact Factor 2.8 CiteScore 5.5



About the Journal

Message from the Editor-in-Chief

You are invited to contribute either a research article or a comprehensive review for consideration and publication in *Processes* (ISSN 2227-9717). *Processes* is published in open access format – research articles, reviews, and other content are released on the internet immediately after acceptance. The scientific community and the general public have unlimited, free access to the content. As an open access journal, *Processes* is supported by the authors and their institutes through the payment of article processing charges (APCs) for accepted papers. We would be pleased to welcome you as one of our authors.

Editor-in-Chief

Prof. Dr. Giancarlo Cravotto

Department of Drug Science and Technology, University of Turin, Via P. Giuria 9, 10125 Turin, Italy

Author Benefits

Open Access:

free for readers, with article processing charges (APC) paid by authors or their institutions.

High Visibility:

indexed within Scopus, SCIE (Web of Science), Ei Compendex, Inspec, AGRIS, and other databases.

Journal Rank:

CiteScore - Q2 (Chemical Engineering (miscellaneous))

